

IN THE SPECIFICATION

Please replace the paragraph beginning at page 53, line 1 with the following rewritten paragraph:

With the aerial image measurement unit 59' indicated in FIG. 3, on measuring the projected image (aerial image) of the measurement mark PM formed on the reticle R or the reticle mark plate RFM via the projection optical system PL, when the illumination light IL having passed through the projection optical system P1 illuminates the slit plate 90 that structure the aerial image measurement unit ~~[[591]]~~ 59', the illumination light IL that has passed through the slit 22 on the slit plate 90 is incident on the light entering end 85a of the light guide 85 after passing through the lens 84, the mirror 88, and the lens 86. The light guided by the light guide 85 is guided out of the wafer stage WST via the light transmittance lens 87, after being emitted from the outgoing end 85b of the light guide 85. And the light guided outside the wafer stage WST is photo-detected by the optical sensor 24 via the photodetection lens 89, and the photoelectric conversion signals (light amount signals) P from the optical sensor 24 corresponding to the photo-detected amount is sent to the main controller 20.

Please replace the paragraph beginning at page 62, line 26 with the following rewritten paragraph:

In addition, on both edges in the Y-axis direction in the center of the effective irradiation area IAF in the X-axis direction, a glass portion (removed area) around 1 mm square in size where other marks cannot be formed are arranged, and within the removed areas, rotation adjustment marks $PM\theta_1$ and $PM\theta_2$ are formed of chromium and the like. Also, around the center portion of the Y-axis direction of the effective irradiation area IAF, a plurality of mark blocks 62₁ are arranged along in the X-axis direction at a predetermined

interval, for example, of 4 mm (1 mm on the wafer, in the case the projection magnification is 1/4). And other than the mark blocks $[[62_2]]$ 62_1 arranged at an interval of 4 mm, mark blocks 62_2 are arranged at positions capable of being set as a detection point within the effective field of the projection optical system PL that correspond to the irradiating point of the image forming light of the multiple focal position detection system (60a, 60b). Therefore, in this embodiment, when performing for example, measurement of the image plane shape of the projection optical system PL, or measurement for calibration to set the offset with respect to the output of each sensor of the multiple focal position detection system (60a, 60b) or to re-set the origin position (detection base position) and the like by aerial image measurement, it becomes possible to measure the position in the optical axis direction (Z position) of the projection optical system PL with the center of the slit 22 of the slit plate 90. Accordingly, the plane accuracy of the slit plate 90 can be moderately set. Hereinafter, the mark blocks 62_1 and the mark blocks 62_2 will be referred to as mark blocks 62 without any distinction, except for cases when necessary.

Please replace the paragraph beginning at page 63, line 28 with the following rewritten paragraph:

On the reticle mark plate RFM, only one line of the $[[AIS]]$ mark blocks 62 is arranged in the scanning direction (Y-axis direction). In the case of performing aerial image measurement, however, with each point of the projection optical system PL in the scanning direction serving as the detection point, the measurement can be performed by moving the reticle stage RST.

Please replace the paragraph beginning at page 66, line 1 with the following rewritten paragraph:

Within the ~~positive~~ negative type additional mark sub-block [[67b]] 67a, an artificial isolated line mark [[PM₁₇]] PM₇ made up of L/S marks with a duty ratio other than 1:1 such as 1:9 having various line widths, a cuneiform mark [[PM₁₈]] PM₈, and ~~positive~~ negative marks of other isolated lines and the like are arranged. These marks, [[PM₁₇]] PM₇ and [[PM₁₈]] PM₈, are also respectively arranged in the X-axis direction and the Y-axis direction.

Please replace the paragraph beginning at page 67, line 17 with the following rewritten paragraph:

Within the positive type additional mark sub-block 67b, an artificial isolated line mark PM₁₇ made up of L/S marks with a duty ratio other than 1:1 such as 1:9 having various line widths, a cuneiform mark (~~SMP mark~~) PM₁₈, and positive marks of other isolated lines and the like are arranged. These marks, PM₁₇ and PM₁₈, are also respectively arranged in the X-axis direction and the Y-axis direction.

Please replace the paragraph beginning at page 68, line 4 with the following rewritten paragraph:

Besides these marks, within the [[AIS]] mark block 62, marks such as a negative mark (BOX mark) PM₂₁ consisting of a square mark which size is 120 square μm (30 μm on the wafer, in the case the projection magnification is 1/4), a Line in Box mark PM₂₂ (this will be referred to later) are also arranged.